

L Number	Hits	Search Text	DB	Time stamp
1	0	ALD and atomic and layer and deposition and surface and (self adj effect) and (alternating adj exposure)	USPAT	2004/04/28 10:48
2	2	ALD and atomic and layer and deposition and surface and (self adj limiting adj effect) and (alternating adj exposure)	USPAT	2004/04/28 10:53
3	1	("6048790").PN.	USPAT	2004/04/28 10:53
4	1	((("6048790").PN.) and (ALD or atomic or deposition or layer or block or surface or first or second or modifying or selectively or coating or alternating or exposure or self or limiting or effect or subsequent or substrate or ligands or vapor or phase or reactants or relative or oxidation or chemical or physical or growth or modification)	USPAT	2004/04/28 11:00
5	1	("6270572").PN.	USPAT	2004/04/28 11:00
6	1	((("6270572").PN.) and (ALD or atomic or deposition or layer or block or surface or first or second or modifying or selectively or coating or alternating or exposure or self or limiting or effect or subsequent or substrate or ligands or vapor or phase or reactants or relative or oxidation or chemical or physical or growth or modification)	USPAT	2004/04/28 11:03
7	1	("6203613").PN.	USPAT	2004/04/28 11:03
8	1	((("6203613").PN.) and (ALD or atomic or deposition or layer or block or surface or first or second or modifying or selectively or coating or alternating or exposure or self or limiting or effect or subsequent or substrate or ligands or vapor or phase or reactants or relative or oxidation or chemical or physical or growth or modification)	USPAT	2004/04/28 11:04
9	1	("6200893").PN.	USPAT	2004/04/28 11:04
10	1	((("6200893").PN.) and (ALD or atomic or deposition or layer or block or surface or first or second or modifying or selectively or coating or alternating or exposure or self or limiting or effect or subsequent or substrate or ligands or vapor or phase or reactants or relative or oxidation or chemical or physical or growth or modification)	USPAT	2004/04/28 11:05
11	1	("6664192").PN.	USPAT	2004/04/28 11:05
12	1	((("6664192").PN.) and (ALD or atomic or deposition or layer or block or surface or first or second or modifying or selectively or coating or alternating or exposure or self or limiting or effect or subsequent or substrate or ligands or vapor or phase or reactants or relative or oxidation or chemical or physical or growth or modification)	USPAT	2004/04/28 11:08
13	1	("6391785").PN.	USPAT	2004/04/28 11:08
14	1	((("6391785").PN.) and (ALD or atomic or deposition or layer or block or surface or first or second or modifying or selectively or coating or alternating or exposure or self or limiting or effect or subsequent or substrate or ligands or vapor or phase or reactants or relative or oxidation or chemical or physical or growth or modification)	USPAT	2004/04/28 11:08
15	987	438/680	USPAT	2004/04/28 11:09
16	475	438/681	USPAT	2004/04/28 11:09
17	161	438/662	USPAT	2004/04/28 11:09
18	340	438/663	USPAT	2004/04/28 11:09
19	2413	438/622	USPAT	2004/04/28 11:09
20	1243	438/633	USPAT	2004/04/28 11:09
21	2733	438/637	USPAT	2004/04/28 11:09
22	1014	438/638	USPAT	2004/04/28 11:09
23	1171	438/648	USPAT	2004/04/28 11:10
24	254	438/650	USPAT	2004/04/28 11:10
25	1265	438/656	USPAT	2004/04/28 11:10
26	371	438/667	USPAT	2004/04/28 11:10
27	502	438/704	USPAT	2004/04/28 11:10
28	1461	438/706	USPAT	2004/04/28 11:10
29	1277	438/745	USPAT	2004/04/28 11:10

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31	2938	438/692	USPAT	2004/04/28 11:10
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-	2	09/644636	USPAT	2004/04/27 15:14

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